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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR			ATTORNEY DOCKET NO.
09/258,961	03/01/99	JIANG		Т	98-0645.1
_		MM91/1018	一	EXAMINER	
STEPHEN A GRATTON 2764 SOUTH BRAUN WAY LAKEWOOD CO 80228		1431/1010		PAREK ART UNIT	H, N PAPER NUMBER
				2811	1.
				DATE WALLED	10/18/01

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

Office Action Summary

Application No.

Applicant(s 09/258,961

Jiang et al

Examiner

Nitin Parekh

Art Unit 2811



The MAILING DATE of this communication appears	on the cover sheet with the correspondence address
Period for Reply	
A SHORTENED STATUTORY PERIOD FOR REPLY IS SE THE MAILING DATE OF THIS COMMUNICATION.	T TO EXPIRE 3 MONTH(S) FROM
- Extensions of time may be available under the provisions of 37 CFR 1.1	36 (a). In no event, however, may a reply be timely filed
after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a rep	ly within the statutory minimum of thirty (30) days will
 be considered timely. If NO period for reply is specified above, the maximum statutory period communication. 	will apply and will expire SIX (6) MONTHS from the mailing date of this
- Failure to reply within the set or extended period for reply will, by statute	c, cause the application to become ABANDONED (35 U.S.C. § 133).
 Any reply received by the Office later than three months after the mailin earned patent term adjustment. See 37 CFR 1.704(b). 	g date of this communication, even if timely filed, may reduce any
Status	
1) Responsive to communication(s) filed on <u>Jul 27, 20</u>	001
2a) ☑ This action is FINAL . 2b) ☐ This acti	on is non-final.
3) Since this application is in condition for allowance exclosed in accordance with the practice under Ex pa	ccept for formal matters, prosecution as to the merits is arte Quayle35 C.D. 11; 453 O.G. 213.
Disposition of Claims	
4) 🗓 Claim(s) <u>24-36</u>	is/are pending in the applica
4a) Of the above, claim(s)	is/are withdrawn from considera
5)	is/are allowed.
6) 🛭 Claim(s) <u>24-36</u>	is/are rejected.
	is/are objected to.
	are subject to restriction and/or election requirem
Application Papers	,
9) The specification is objected to by the Examiner.	
10) The drawing(s) filed on is/a	re objected to by the Examiner
11) The proposed drawing correction filed on	
12) The oath or declaration is objected to by the Examine	
Priority under 35 U.S.C. § 119 13)□ Acknowledgement is made of a claim for foreign₊prio	rity under 35 U.S.C. & 119(a)-(d)
a) ☐ All b) ☐ Some* c) ☐None of:	my diluci 00 0.3.3. § 113(a)-(u).
1. Certified copies of the priority documents have	been received
2. Certified copies of the priority documents have	
3. Copies of the certified copies of the priority doc	
application from the International Bureau *See the attached detailed Office action for a list of the	(PCT Rule 17.2(a)).
14) ☐ Acknowledgement is made of a claim for domestic pr	
	,
Attachment(s) 15) X Notice of References Cited (PTO-892)	40)
13) Motice of References Cited (P10-892) 16) Notice of Draftsperson's Patent Drawing Review (PTO-948)	18) Interview Summary (PTO-413) Paper No(s).
17) Normation Disclosure Statement(s) (PTO-1449) Paper No(s). 6 and 1	19) Notice of Informal Patent Application (PTO-152) 20) Other:
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DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 24-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over the admitted prior art (APA) in view of Lee et al (US Pat. 5796586) and/or Akram et al (US Pat. 5739585).

Regarding claims 24-26, the admitted prior art (Fig.1A and B; pages 2-4) et al discloses a semiconductor package comprising :

- a substrate comprising a first surface, a second surface, a plurality of conductors and ball bonding pads formed on the first surface and a bonding opening from the first surface to the second surface
- a semiconductor die having a first outline and a face on the bonding opening bonded to the second surface
- first mask on the first surface of the substrate comprising a plurality of via openings aligned with the ball bonding pads

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- a second mask substantially covering a second surface of the substrate

- an adhesive layer between the die and the substrate in the die attach area to bond the face to the second mask and the substrate,

- a plurality of wires placed through the bonding opening and wire bonded to the die and to the conductors

- an encapsulating material/resin on the die and the second mask, and
- a glob top in the bonding opening encapsulating the wires.

The admitted prior art (APA) fails to specify directly bonding the die to the second surface and having an opening in the second mask including a second outline corresponding to but only slightly larger than the first outline.

Lee et al teach using a second mask having an opening through the mask with a second outline (see hatched mask area 218' with a second outline- Fig. 7; Col. 7, line 55) substantially matching that of the first outline with an open die attach area (see first outline area 204- Fig. 7) on the second surface so that the die is directly bonded to the second surface so that the solder mask can provide a better resistance against cracking at the substrate surface (Fig. 7 and Fig. 1-6; Col. 1-8). Lee et al further teach using solder mask patterns where the second outline is larger than the die attach region (Fig. 1A and B). It is a matter of design choice to select the outline/pattern of the solder mask area to achieve the desired bonding with the encapsulant and adhesion. Furthermore, Lee et al disclose die attach area, conventionally, not being covered with solder mask so that the die attaches directly to the substrate surface (Col. 8, line 7).

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Akram et al teach using conventional die attach technique where the die (18 in Fig. 10; Col. 9, line 24) is face-bonded to the second surface using typical adhesive/fill materials (Col. 4, line 26) such as an epoxy, silicone, polyimide, other dielectric material, etc.

Therefore, it would have been obvious to a person of ordinary skill in the art at the time invention was made to use a second mask having an opening and a second outline corresponding to but only slightly larger than the first outline so that the die is bonded directly to the second surface to prevent the cracking of the solder mask and to achieve the desired bonding with the encapsulant using Lee et al and Akram et al's teachings in the admitted prior art.

3. Claims 27-29 are rejected under 35 U.S.C. 103(a) as being unpatentable over the admitted prior art (APA) in view of Lee et al (US Pat. 5796586) and/or Akram et al (US Pat. 5739585).

The combined teachings of Lee et al and Akram et al apply to claims 27-29 as explained above for claims 24-26.

4. Claims 30-33 are rejected under 35 U.S.C. 103(a) as being unpatentable over the admitted prior art (APA) in view of Lee et al (US Pat. 5796586) and/or Akram et al (US Pat. 5739585).

The combined teachings of Lee et al and Akram et al apply to claims 30-33 as explained above for claims 24-26.

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5. Claims 34-36 are rejected under 35 U.S.C. 103(a) as being unpatentable over the admitted prior art (APA) in view of Lee et al (US Pat. 5796586) and/or Akram et al (US Pat. 5739585).

The combined teachings of Lee et al and Akram et al apply to claims 34-36 as explained above for claims 24-26.

Response to Arguments

- 6. Applicant's arguments filed on 07-27-01 have been fully considered but they are not persuasive.
- A. Applicant contends that Lee et al's solder mask as shown in Fig. 3-5, only covers the edges of the substrate. However, as explained above for claims 24-26, Lee et al teach using a second mask having an opening through the mask with a second outline substantially matching that of the first outline with an open die attach area (see first outline area 204- Fig. 7). This configuration provides a better resistance against cracking at the substrate surface and improved adhesion with an encapsulating resin (Col. 7, line 62; Col. 8, line 5). Lee et al further teach using solder mask patterns where the second outline can be larger than the die attach region (Fig. 1A and B). It is a matter of design choice in the chip packaging and encapsulation technology art to select the parameters such as an outline/pattern of the solder mask area, thickness, adhesion properties, etc. to achieve the desired bonding with the encapsulant and adhesion. Therefore, it

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would have been obvious to a person of ordinary skill in the art to select the area/coverage of a second mask having a second outline corresponding to but only slightly larger than the first outline using Lee et al's mask pattern in the APA.

B. Applicant contends that Lee et al's solder mask is configured to protect the circuit traces. However, Lee et al further teach that the solder mask provides better resistance to cracking than typical adhesives (Col. 7, line 60) on any surface on the substrate and liquid photoimageable solder mask such as PSR 4000 from Taiyo Corporation (the same material as described in the specification pp.10) provides good adhesion with the encapsulating materials (Col. 8, line 5). Furthermore, Lee et al disclose that conventionally the die attach area is not covered by the solder mask. Therefore, Lee et al's teaching is applied to the APA to improve the cracking resistance and adhesion.

Conclusion

7. Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

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A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Papers related to this application may be submitted directly to Art Unit 2811 by facsimile transmission. Papers should be faxed to Art Unit via Technology Center 2800 fax center located in Crystal Plaza 4, room 4C23. The faxing of such papers must conform with the notice published in the Official Gazette, 1096 OG 30 (15 November 1989).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Nitin Parekh whose telephone number in (703) 305-3410. The examiner can be normally reached on Monday-Friday from 08:30 am-5:00 pm.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas, can be reached on (703) 308-2772. The fax number for the organization where this application or proceeding is assigned is (703) 308-7722 or 7724.

Nitin Parekh

10-12-01

TOM THOMAS
SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 2800